

# **3DCoB: A new design approach for Monolithic 3D Integrated Circuits**

**CEA-Leti, Grenoble, FRANCE**

**Hossam SARHAN, Sébastien THURIES, Olivier BILLOINT & Fabien CLERMIDY**

## Outline:

- **Introduction to 3D Integrated Circuits**
- **3D Monolithic Integration (3DMI) Technology**
- **Previous 3DMI Approaches**
- **3D Cell-on-Buffer (3DCoB) Approach**
- **3DCoB Design Flow**
- **Results and Conclusion**

## Outline:

- **Introduction to 3D Integrated Circuits**
- 3D Monolithic Integration (3DMI) Technology
- Previous 3DMI Approaches
- 3D Cell-on-Buffer (3DCoB) Approach
- 3DCoB Design Flow
- Results and Conclusion

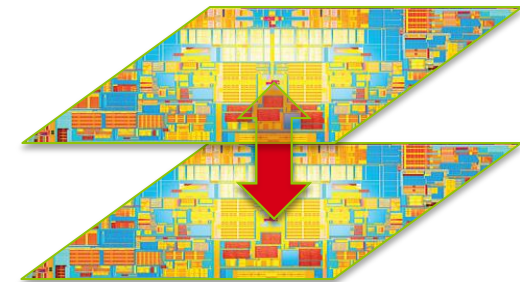
# Introduction to 3D Integrated Circuits

## Why logic-on-logic 3D stacking ?

- Better performances (shorten wires → less delay)
  - Less power (shorten wires → less parasitics)
  - Smaller footprint.
- > **Overcomes technology scaling limitation !**



2D IC



3D IC

## 3D Technology Limitations:

- Large size of the 3D interconnects (area overhead).
- Limited number of vertical interconnects (3D-Vias).
- 3D interconnects parasitics (resistance/capacitance).

# 3D Integration Technologies

- **Parallel Integration**

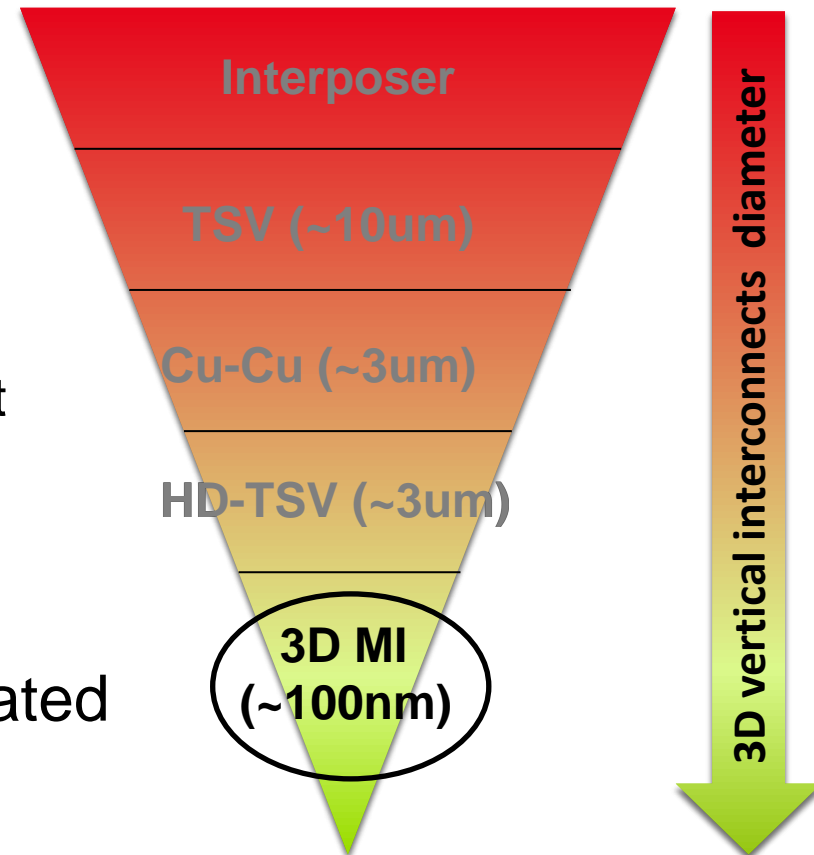
Dies fabricated separately then vertically stacked, such as:

- Passive/Active Interposer
- Through-Silicon-Via (TSV)
- Copper-to-Copper (Cu-Cu) contact
- High-Density TSVs

- **Sequential Integration**

Second transistor layer is fabricated directly on the top of first one.  
(Cold process)

- **3D Monolithic Integration (3DMI)**



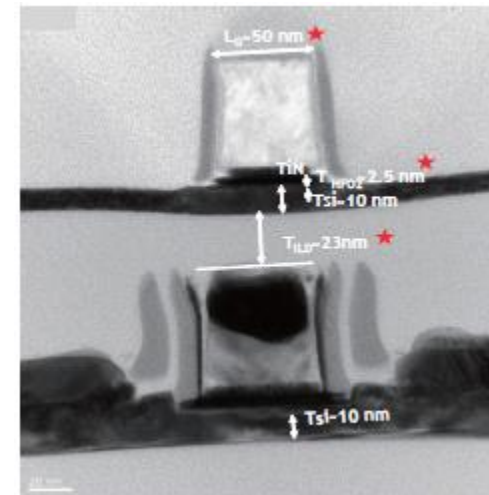
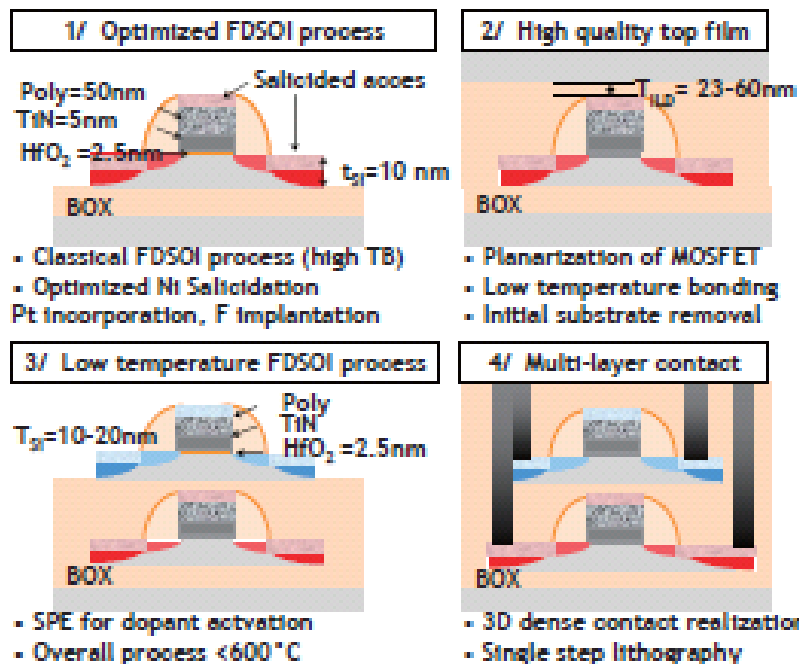
## Outline:

- Introduction to 3D Integrated Circuits
- **3D Monolithic Integration (3DMI) Technology**
- Previous 3DMI Approaches
- 3D Cell-on-Buffer (3DCoB) Approach
- 3DCoB Design Flow
- Results and Conclusion

# Monolithic 3D Integration Technology

- + Second transistor layer is fabricated sequentially on top of the first one.
- + High alignment precision, and very small 3D vias

→ 30 times smaller compared to state-of-the-art “HD-TSV & Cu-Cu”



[\*] P. Batude et al., "Demonstration of low-temperature 3D sequential FDSOI integration down to 50 nm gate length" VLSI Technology (VLSIT), symposium on, IEEE, 2011.

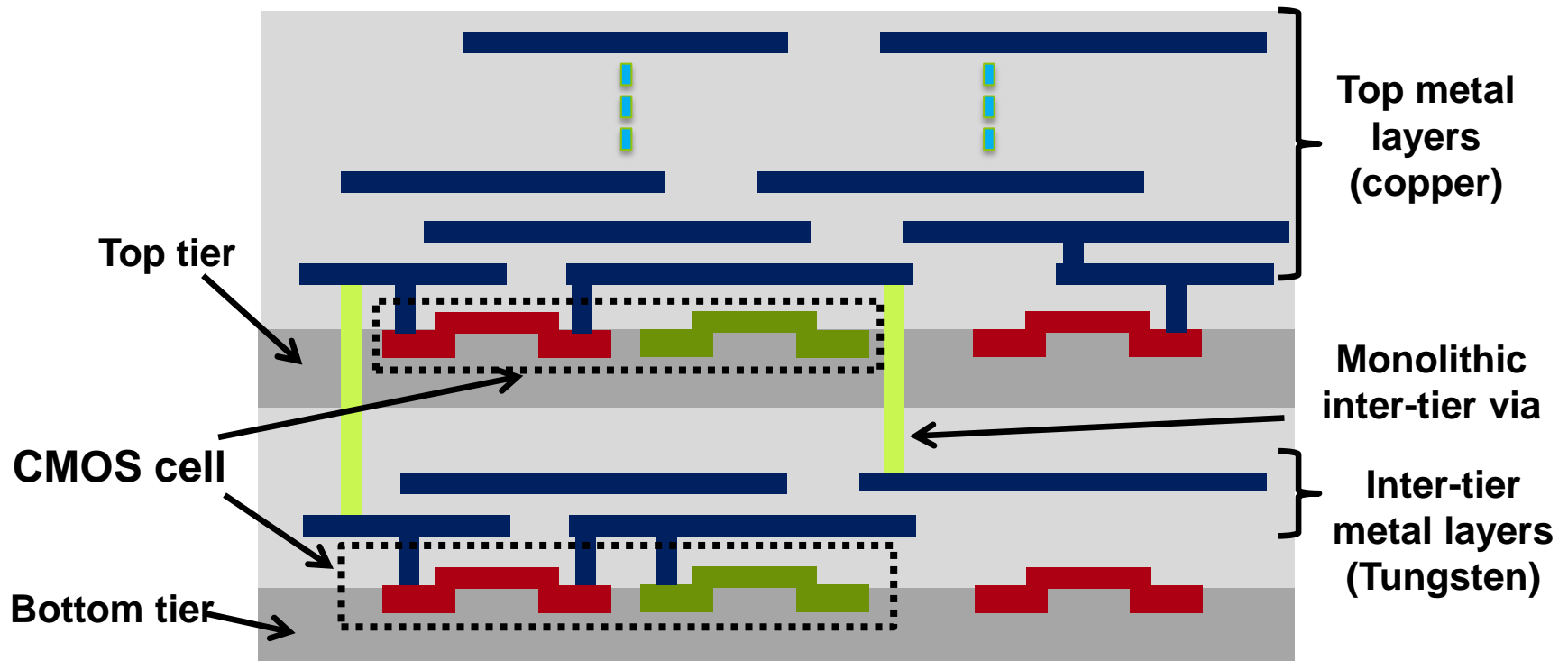
## Outline:

- Introduction to 3D Integrated Circuits
- 3D Monolithic Integration (3DMI) Technology
- **Previous 3DMI Approaches**
- 3D Cell-on-Buffer (3DCoB) Approach
- 3DCoB Design Flow
- Results and Conclusion



# Previous 3DMI Approaches (1/2)

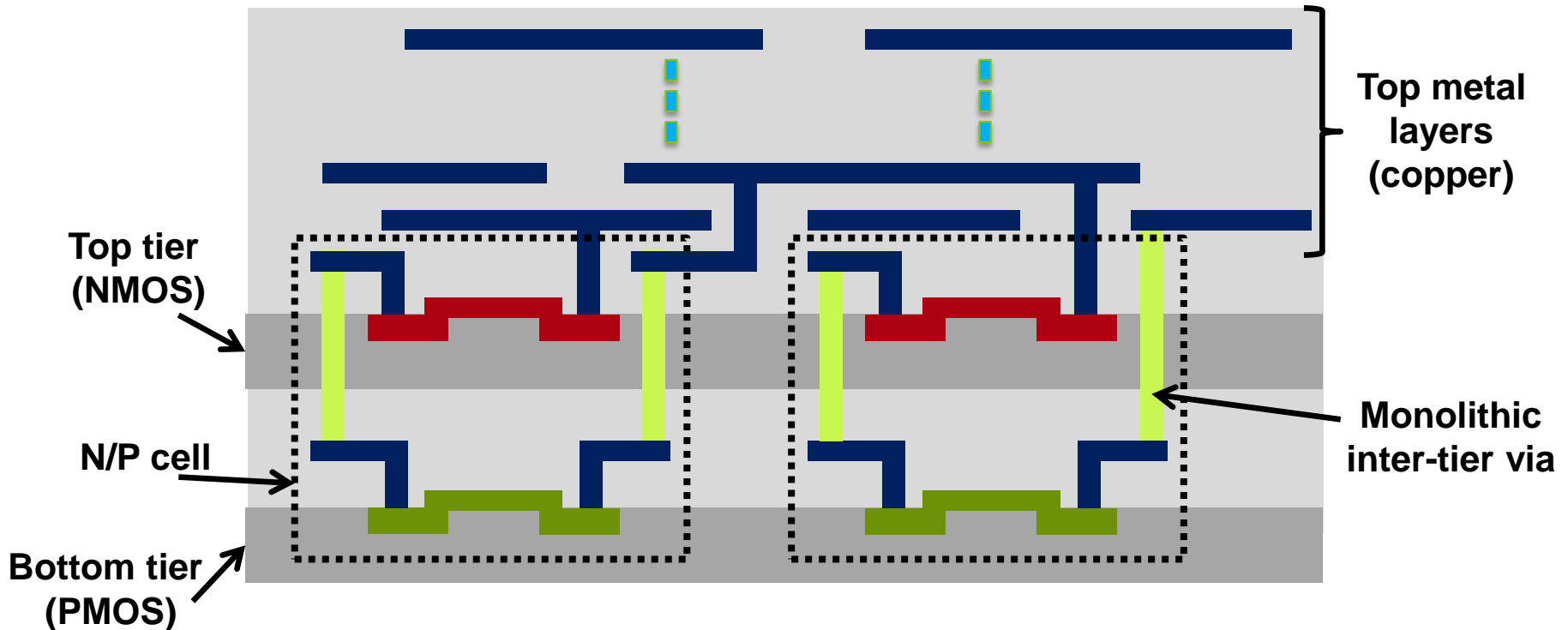
## 1. Gate-level approach (Cell-on-Cell)



- + Using 2D CMOS standard cells.
- Incompatible with the conventional 2D design flow.

# Previous 3DMI Approaches (2/2)

## 2. Transistor-level Integration (NMOS/PMOS)



- + Compatible with the conventional 2D design flow.
- 3D NMOS-over-PMOS (N/P) cells are needed.

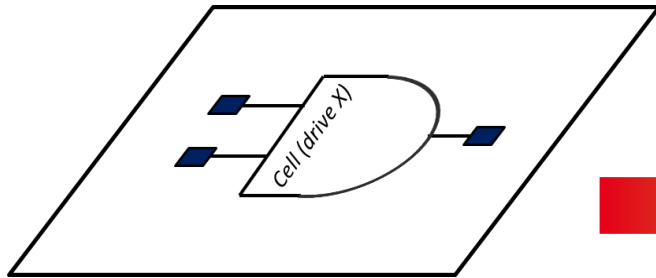
## Outline:

- Introduction to 3D Integrated Circuits
- 3D Monolithic Integration (3DMI) Technology
- Previous 3DMI Approaches
- **3D Cell-on-Buffer (3DCoB) Approach**
- 3DCoB Design Flow
- Results and Conclusion

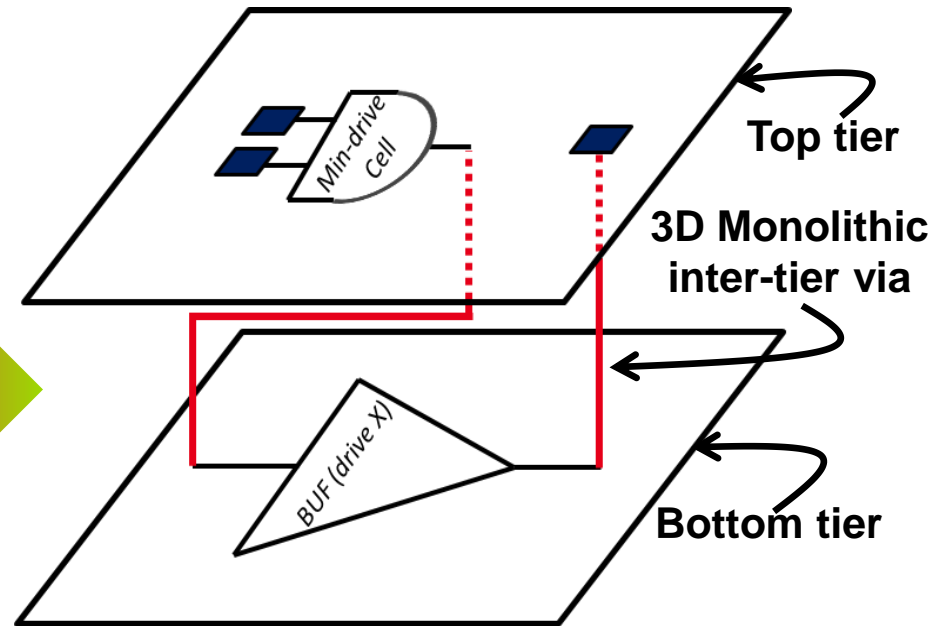
# Proposed Approach: “3D Cell-on-Buffer”

- Split non-minimum drive cells into 2 tiers:
  - Min drive logic cell in top tier.
  - Driving buffer into bottom tier.

2D Non-MIN Drive Cell



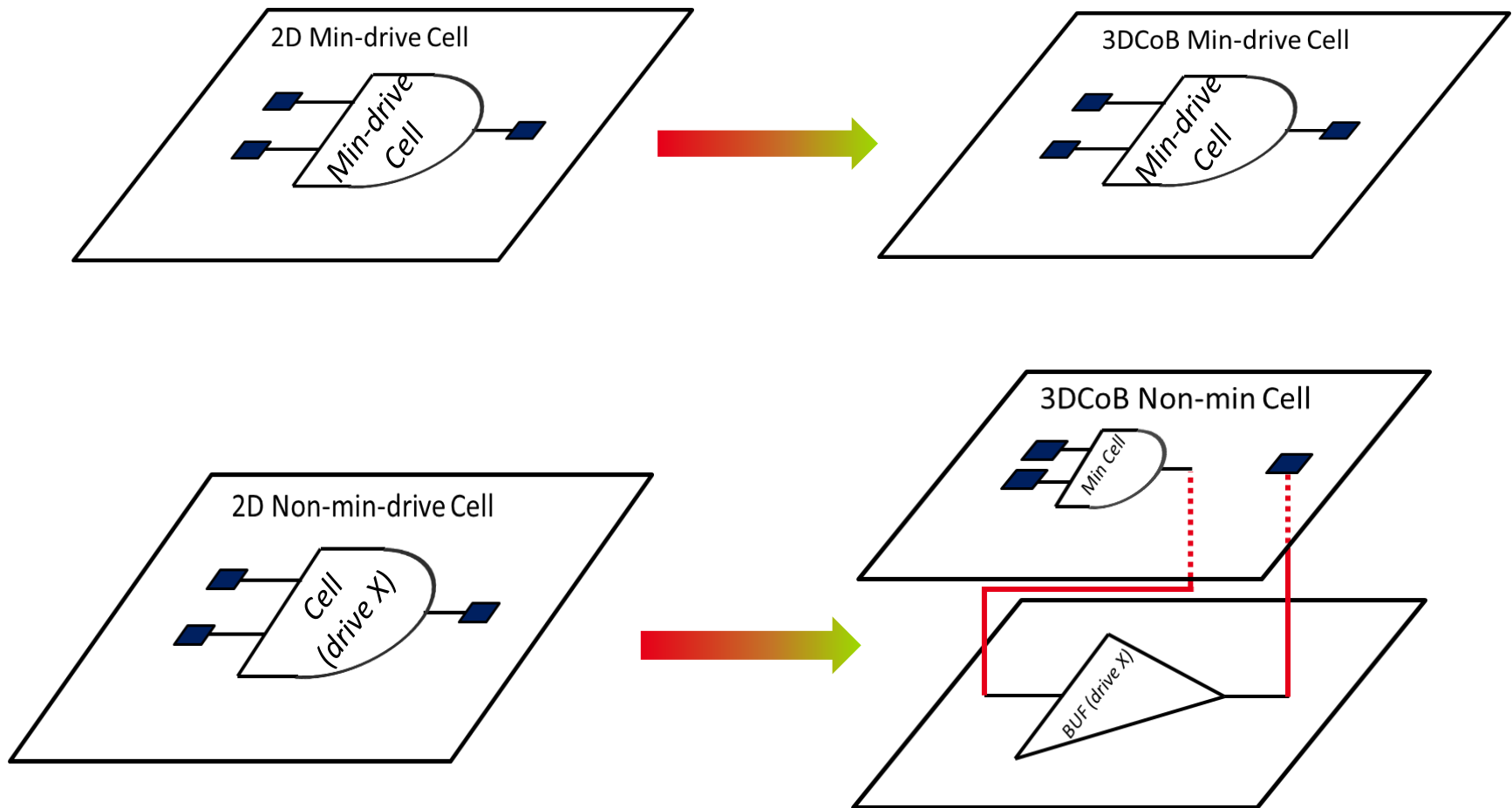
3DCoB Non-MIN Drive Cell



- Min drive cells are still in 2D (planar).

# Proposed Approach: "3D Cell-on-Buffer"

- Consequently the 3DCoB set of cells will be:



# Comparison with other approaches

“3D Cell-on-Buffer (3DCoB)” vs. “Cell-on-Cell” vs. “N/P”

	N/P	Cell-on-Cell	<b>3DCoB (our work)</b>
2D Design flow compatibility	Yes	No	<b>Yes</b>
Using 2D standard cells	No	Yes	<b>Yes</b>
Using inter-tier routing metal layers	No	Yes	<b>No</b>
Usage of inter-tier vias	In every cell	Between cells (if req.)	<b>Only in the 3D cells</b>

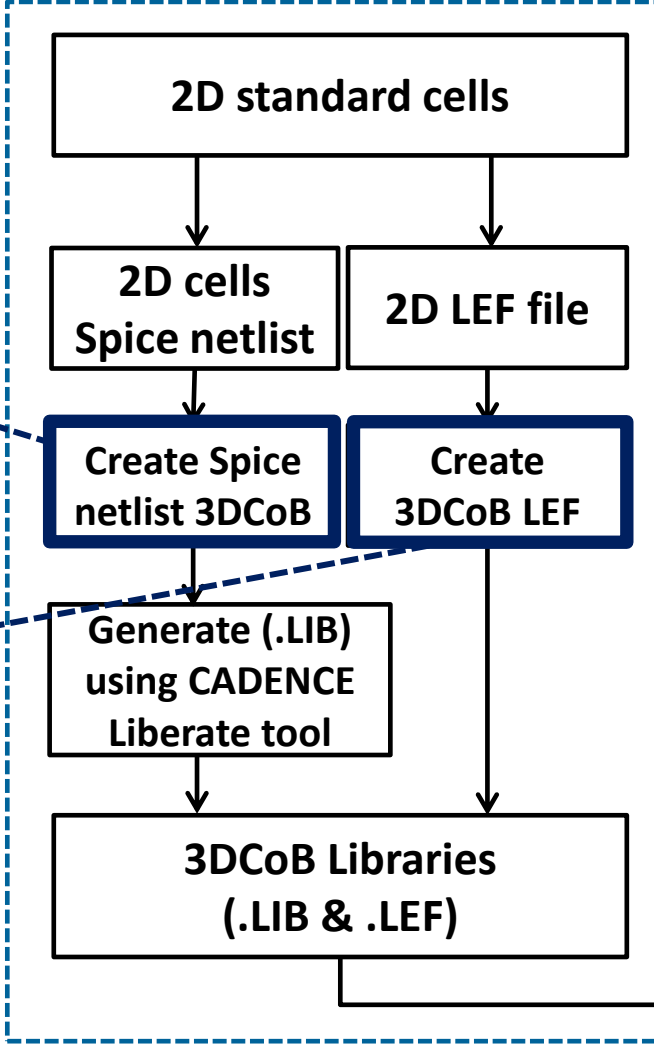
## Outline:

- Introduction to 3D Integrated Circuits
- 3D Monolithic Integration (3DMI) Technology
- Previous 3DMI Approaches
- 3D Cell-on-Buffer (3DCoB) Approach
- **3DCoB Design Flow**
- Results and Conclusion

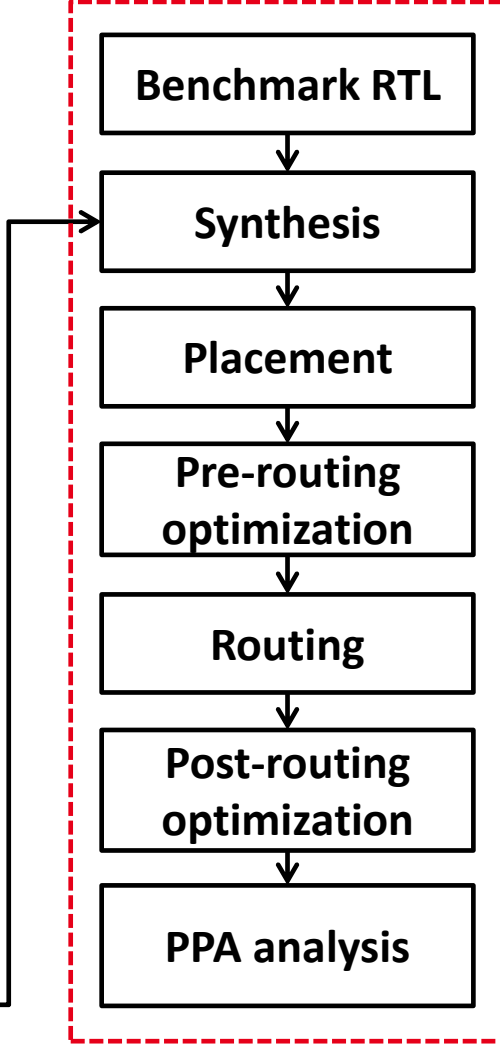
# 3DCoB Design Flow

By connecting in series “the min-drive cell of the same type” with “the equivalent-drive buffer”

By determining the area of the 3DCoB cells



3DCoB Libraries generation



Conventional 2D implementation flow (CADENCE tool)



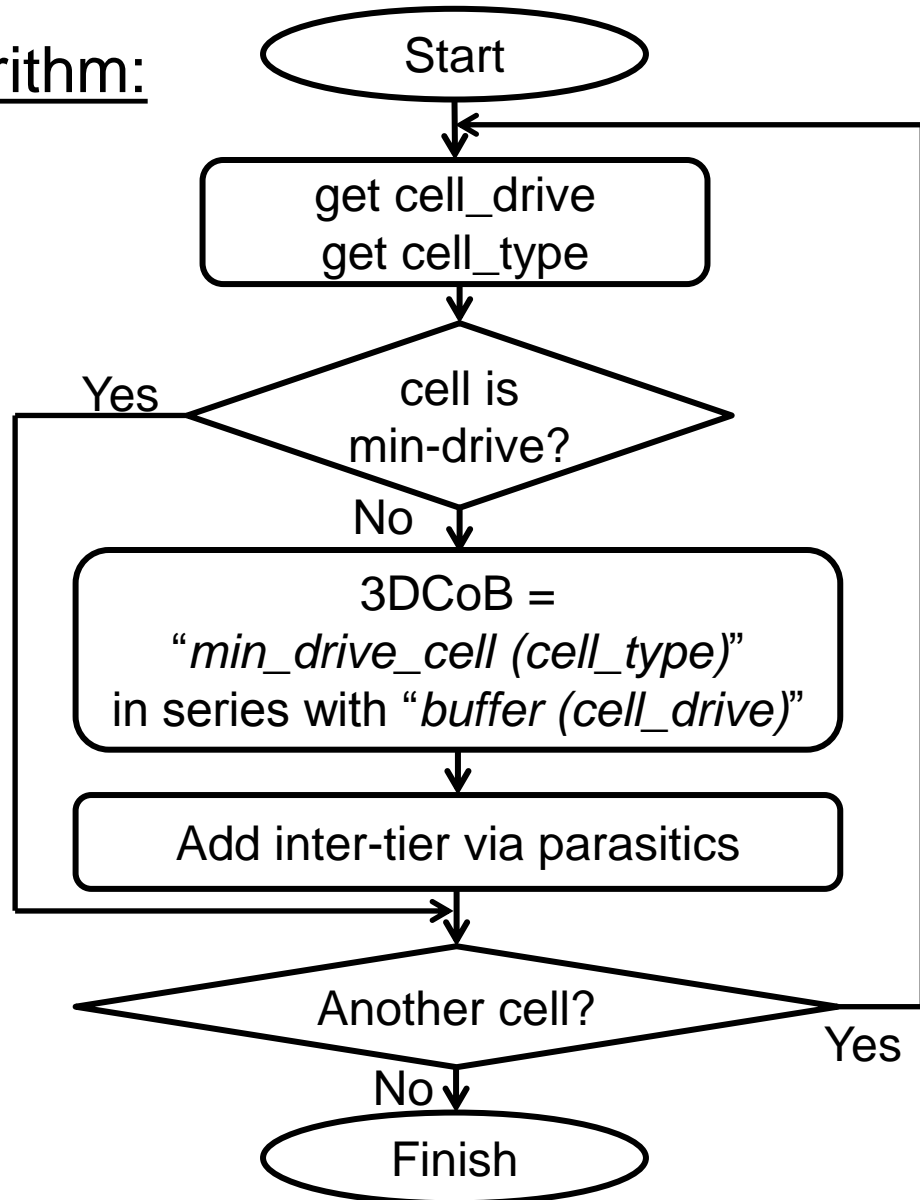
# 3DCoB Design Flow : LIB generation

## 3DCoB Cells generation algorithm:

### Example: “AND2x33” →

- The type is 2-input AND gate “AND2x”
- Cell drive = “33”
- The min-drive cell of the 2-input AND is “AND2x8”
- The equivalent-drive buffer is “BUFx33”

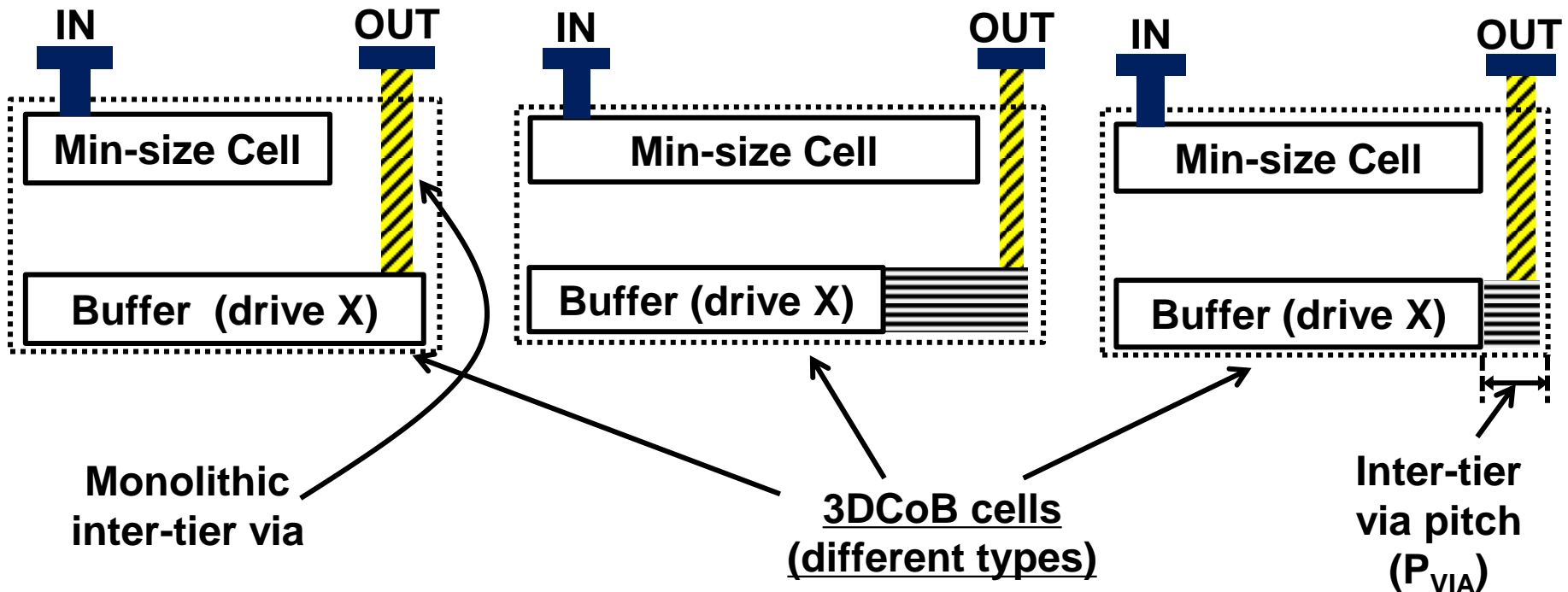
3DCoB cell for AND2x33 is:  
“AND2x8” in series “BUFx33”



# 3DCoB Design Flow: LEF generation

- Area of 3D Cell-on-Buffer Cells depends on:
  - Area of the buffer ( $A_{BUF}$ ) compared to the min-drive cell ( $A_{MIN-CELL}$ ).
  - Inter-tier Via pitch ( $P_{VIA}$ )

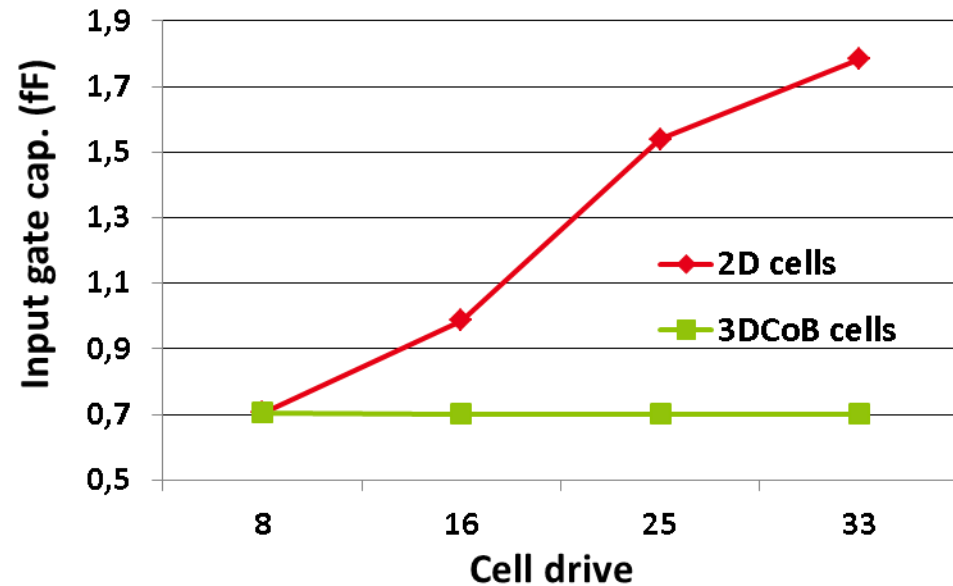
$$Area_{3DCoB} = \begin{cases} A_{BUF}, & (A_{MIN-CELL} + P_{VIA}) < A_{BUF} \\ \max(A_{MIN-CELL}, A_{BUF}) + P_{VIA}, & (A_{MIN-CELL} + P_{VIA}) \geq A_{BUF} \end{cases}$$



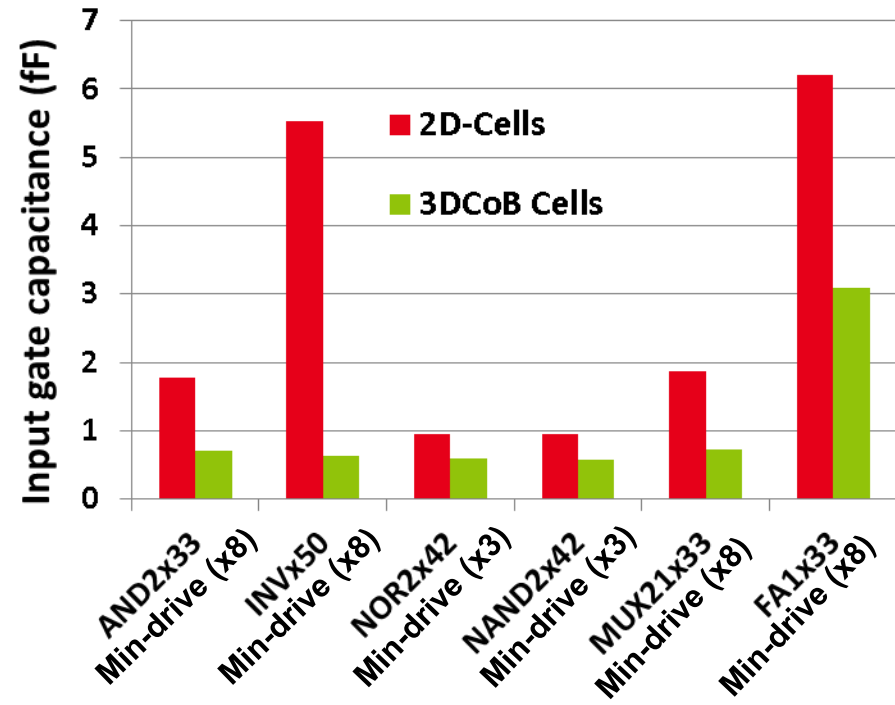
## Outline:

- Introduction to 3D Integrated Circuits
- 3D Monolithic Integration (3DMI) Technology
- Previous 3DMI Approaches
- 3D Cell-on-Buffer (3DCoB) Approach
- 3DCoB Design Flow
- **Results and Conclusion**

# Results: 3DCoB Input Capacitance



2-input AND gate at different drives



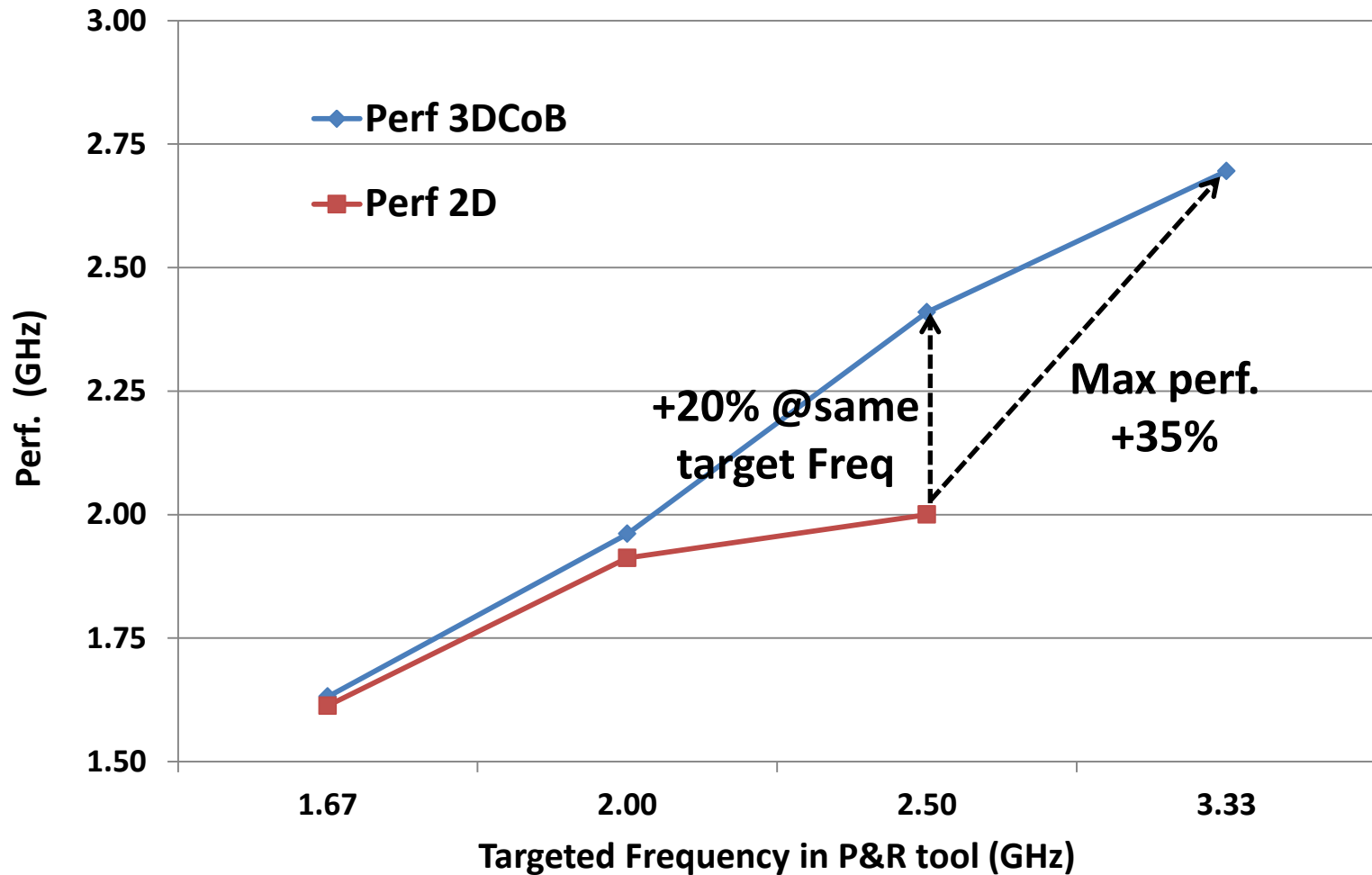
# Results: FFT & AES blocks in 28nm FDSOI

		# Std Cells	Cell Density	Perf <sup>1</sup> (GHz)	Perf <sup>1</sup> Gain (%)	Power <sup>2</sup> (mW)	Power <sup>2</sup> Loss (%)
<b>FFT</b> Target freq=1.67GHz Area=0.027mm <sup>2</sup>	2D	24771	95%	1.33	--	36.001	--
	3DCoB	26210	93%	1.51	13.53%	37.452	-4.03%
<b>AES</b> Target freq=2.55GHz Area= 0.119mm <sup>2</sup>	2D	164174	89%	2.00	--	249.774	--
	3DCoB	166749	90%	2.41	20.5%	263.165	-5.36%

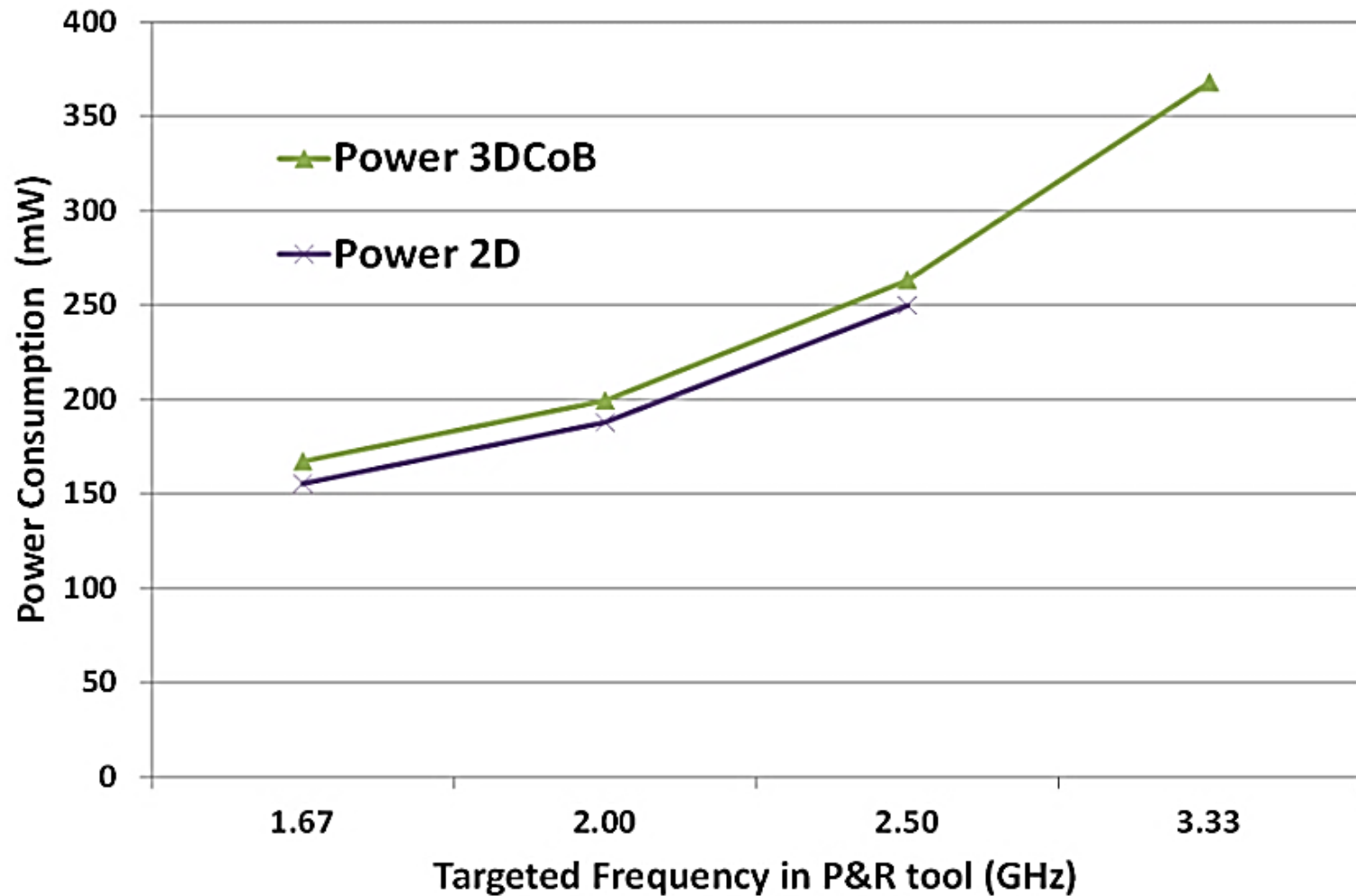
<sup>1</sup> Performance is measured as the effective clock frequency (target clock period without slack time)

<sup>2</sup> Power is calculated with activity factor (0.15) using SoC Encounter power reports

# Results: Performance of AES-128 block



# Results: Power of AES-128 block



- 3D Cell-on-Buffer (3DCoB) architecture shows:
  - Improvement in performances (~ 20 to 35%)
  - Compatible design flow with 2D EDA tools.
  - Limited impact on power consumption.
  - No need for inter-tier routing metal layer in the bottom tier.
  - No clock synchronization issue between the two tiers.
- Thermal impact needs to be studied as well !
  - Targeted low-power applications will limit this issue





# Thank You Questions ?



**leti**

Centre de Grenoble  
17 rue des Martyrs  
38054 Grenoble Cedex

**list**

Centre de Saclay  
Nano-Innov PC 172  
91191 Gif sur Yvette Cedex

# leti

Centre de Grenoble  
17 rue des Martyrs  
38054 Grenoble Cedex



# list

Centre de Saclay  
Nano-Innov PC 172  
91191 Gif sur Yvette Cedex

